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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/767,195	01/28/2004	Satish Sundar	8243/DSM/BCVD/JW	5733
44182 75	08/03/2006	EXAMINER		INER
PATTERSON & SHERIDAN, LLP			DHINGRA, RAKESH KUMAR	
APPLIED MATERIALS INC 595 SHREWSBURY AVE		ART UNIT	PAPER NUMBER	
SUITE 100			1763	
SHREWSBURY, NJ 07702			DATE MAILED: 08/03/2006	

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)			
	10/767,195	SUNDAR, SATISH			
Office Action Summary	Examiner	Art Unit			
	Rakesh K. Dhingra	1763			
The MAILING DATE of this communication app Period for Reply	ears on the cover sheet with the c	orrespondence address			
A SHORTENED STATUTORY PERIOD FOR REPLY WHICHEVER IS LONGER, FROM THE MAILING DA  - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication.  - If NO period for reply is specified above, the maximum statutory period w  - Failure to reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMUNICATION 36(a). In no event, however, may a reply be tim rill apply and will expire SIX (6) MONTHS from cause the application to become ABANDONE	<b>N</b> . nely filed the mailing date of this communication. D (35 U.S.C. § 133).			
Status					
1) Responsive to communication(s) filed on <u>05 Ju</u>	<u>ne 2006</u> .				
,					
3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is					
closed in accordance with the practice under E	x parte Quayle, 1935 C.D. 11, 45	53 O.G. 213.			
Disposition of Claims					
4)⊠ Claim(s) <u>1-18 and 23-25</u> is/are pending in the application.					
4a) Of the above claim(s) 6,7,9 and 12-18 is/are withdrawn from consideration.					
5) Claim(s) is/are allowed.					
6)⊠ Claim(s) <u>1-5,8,10,11 and 23-25</u> is/are rejected.					
7) Claim(s) is/are objected to. 8) Claim(s) are subject to restriction and/or	r election requirement				
o) Claim(s) are subject to restriction and/or	election requirement.				
Application Papers					
9)☐ The specification is objected to by the Examine					
10) The drawing(s) filed on 28 January 2004 is/are:					
Applicant may not request that any objection to the o					
Replacement drawing sheet(s) including the correcting 11) The oath or declaration is objected to by the Expression is a specific to be a specific to the second sec					
	ammer. Note the attached Office	Action of formal 10-102.			
Priority under 35 U.S.C. § 119					
12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).					
a) All b) Some * c) None of:	have been received				
<ul><li>1 Certified copies of the priority documents</li><li>2 Certified copies of the priority documents</li></ul>		on No			
3. Copies of the certified copies of the prior					
application from the International Bureau		3			
* See the attached detailed Office action for a list of		d.			
Attachment(s)					
1) Notice of References Cited (PTO-892)	4) Interview Summary				
<ul> <li>2) Notice of Draftsperson's Patent Drawing Review (PTO-948)</li> <li>3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08)</li> </ul>	Paper No(s)/Mail Da 5) Notice of Informal P	ate ratent Application (PTO-152)			
Paper No(s)/Mail Date	6) Other:				

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### **DETAILED ACTION**

## Response to Arguments

Applicant's arguments filed 6/5/06 have been fully considered but they are not persuasive as explained hereunder.

1) Claims 1, 2 [35 USC 102 (a)]

Applicant argues that Arai does not teach claim limitation "---at least three elements movably coupled to a substrate support in a spaced apart relation proximate a perimeter of the substrate support, and a first end of each element adapted to engage an edge of the substrate".

Examiner responds that as explained below, Arai teaches all limitations of claim 1 including "---at least three lift pins (elements) 13 movably coupled to a susceptor (substrate support) 12 in a spaced apart relation (total of three lift pins spaced apart from each other) proximate a perimeter of the susceptor (substrate support) 12, and a first end of each lift pin (element) 13 adapted to engage an edge of the substrate 20 (Figures 1, 2 and paragraphs 0021-0029)".

Applicant also contends that "at least three elements" recited in claim 1 are not anticipated by "lift pins" of Arai and that "elements" of claim 1 and "lift pins" of claim 14 should be given different meaning.

Examiner responds that limitations of claim 14 (that is, pertaining to lift pins) have no relevance to the rejection of claim 1. Accordingly rejection of claims 1, 2 under 35 USC 102 (a) is maintained.

2) Claims 3, 4 [35 USC 103 (a)]

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Applicant argues that Hirose also does not teach the elements of claim 1 that is "---at least three elements movably coupled to a substrate support in a spaced apart relation proximate a perimeter of the substrate support, and a first end of each element adapted to engage an edge of the substrate" and therefore claims 3, 4 are patentable being dependent upon claim 1.

Examiner responds that as explained above Arai does teach all limitations of claim 1 and thus rejection of claims 3, 4 under 35 USC103 (a) is maintained as explained below.

3) Claims 5 and 10-11 [35 USC 103 (a)]

Applicant contends that combining Meares with Arai and Hirose would not yield the claim 1 limitation "---at least three elements movably coupled to a substrate support in a spaced apart relation proximate a perimeter of the substrate support, and a first end of each element adapted to engage an edge of the substrate", and this claims 5, 10-11 are patentable as being dependent upon claim 1.

Examiner responds that claim 1 limitation "---at least three elements movably coupled to a substrate support in a spaced apart relation proximate a perimeter of the substrate support, and a first end of each element adapted to engage an edge of the substrate" is taught by Arai as explained above. Reference by Meares is included in rejection regarding claim limitation "wherein each of at least three elements is adapted to rotate about an axis parallel to a plane of substrate support. Thus rejection of claims 5, 10-11 under 35 USC 103 (a) is maintained.

3) Claim 8 [35 USC 103 (a)]

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Applicant argues that Gibson also fails to teach claim 1 limitation "---at least three elements movably coupled to a substrate support in a spaced apart relation proximate a perimeter of the substrate support, and a first end of each element adapted to engage an edge of the substrate" and thus claim 8 is patentable as being dependent upon claim 1.

Examiner responds that as explained above, Arai teaches claim 1 limitation "---at least three elements movably coupled to a substrate support in a spaced apart relation proximate a perimeter of the substrate support, and a first end of each element adapted to engage an edge of the substrate". Thus rejection of claim 8 under 35 USC 103 (a) is maintained.

New claims 23-25 are also rejected under 35 USC 103 (a) as explained below.

# Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(a) the invention was known or used by others in this country, or patented or described in a printed publication in this or a foreign country, before the invention thereof by the applicant for a patent.

Claims 1, 2 are rejected under 35 U.S.C. 102(a) as being anticipated by Arai (US PGPUB No. 2003/0075109).

Regarding Claim 1: Arai teaches an apparatus (Figures 1, 2) comprising:

a reaction chamber (chamber body) 11 having a bottom;

a vertically moveable susceptor (substrate support) 12 disposed in the chamber body and having a first side adapted to support a wafer (substrate) 20 during processing,

there-through (Paragraph 0022).

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at least three lift pins (elements) 13 movably coupled to the substrate support in a spaced-apart relation proximate a perimeter of the substrate support; a first end of each lift pin 13 extending beyond the first side 12c of the substrate support, the first end adapted to engage an edge of the substrate 20, and a second end of each element positioned below a second side of the substrate support 12 and adapted to engage the bottom of the chamber body when the substrate is in a lowered position (Paragraphs 021, 0022).

Regarding Claim 2: Arai teaches the susceptor (substrate support) 12 further comprises at least three apertures 12b adapted to receive the three lift pins 13

## Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 3, 4, 23, 25 are rejected under 35 U.S.C. 103(a) as being unpatentable over Arai (US PG PUB No. 2003/0075109) in view of Hirose et al (US Patent No. 6,104,002).

Regarding Claims 3, 4: Arai teaches all limitations of the claim except the three apertures disposed through the substrate support are sized to accommodate a predefined radial displacement of the at least three elements.

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Hirose et al teach an apparatus (Figures 3-5) that comprises a chamber 21 having a support plate (substrate support) 22 that has plurality of holes 28 for passage of support pins 30 and where the holes 28 are large enough to permit horizontal movement (includes radial) of pins 30. Hirose et al further teach that extent of horizontal (includes radial) movement can be set (pre-defined) as per other relevant considerations like length of support pin, and width of leg portion 30a. Hirose et al also teach that support pins 30 are movable in up/down direction through support plate (substrate support) 22, due to movement of holding member 31 that is attached to lift mechanism 33 (Column 5, line 20 to Column 6, line 5).

Therefore it would have been obvious to one of ordinary skill in the art at the time of the invention to provide for radial displacement of pins in the holes in substrate support as taught by Hirose et al in the apparatus of Arai to reduce particle generation as a result of contact between support pin and internal wall of the hole in the substrate support (Column 2, lines 1-35).

Regarding Claim 23: Hirose et al teach that first end of each support pin (element) 30 is laterally movable (Figures 3-5 and column 2, lines 25-35 and column 5, lines 20-65). Regarding Claim 25: Arai teaches (Figure 1, 2) that maximum height (elevation) of first end of pins (elements) 13 with respect to first side of susceptor (substrate support) 12 is fixed (paragraphs 0021-0029).

Claims 5, 10, 11 are rejected under 35 U.S.C. 103(a) as being unpatentable over Arai (US PG PUB No. 2003/0075109) in view of Hirose et al (US Patent No. 6,104,002) as applied to Claim 4 and further in view of Meares et al (EP 0290218).

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Regarding Claim 5: Arai in view of Hirose et al teaches all limitations of the claim except that each of the at least three elements is adapted to rotate about an axis substantially parallel to a plane of the substrate support.

Meares et al teach an apparatus (Figure 8) that includes a platen (substrate support) P that supports wafer W with the help of plurality of fingers (elements) f1 – f4 and where the fingers f experience rotational motion about pivot arc Pa when the wafer is gripped by the fingers (Column 8, lines 10-30).

Therefore it would have been obvious to one of ordinary skill in the art at the time of the invention to provide for rotational movement of fingers (elements) as taught by Meares et al in the apparatus of Arai in view of Hirose et al to properly engage and disengage the wafer (Column 1, lines 45-50).

Regarding Claims 10,11: Meares et al teach that fingers f are biased (pivoted) about Pa by the resilient spring portion (biasing members) 41a that are also coupled around pivot Pa. Meares et al do not teach that the resilient spring portions (biasing members) are torsion springs, but teach that geometry of collet 41 (means including resilient spring portions) could be selected (could include torsion springs also) depending upon other related parameters (Column 7, lines 10-330).

Claim 8 is rejected under 35 U.S.C. 103(a) as being unpatentable over Arai (US PG PUB No. 2003/0075109) in view of Hirose et al (US Patent No. 6,104,002) as applied to Claim 4 and further in view of Gibson et al (US PGPUB No. 2003/0118741).

Regarding Claim 8: Arai in view of Hirose et al teaches all limitations of the claim except that second end of each of the elements comprises a roller.

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Gibson et al teach a substrate support apparatus where due to vertical space constraint, rollers are attached to ends of vertically oriented lift pins that move wedges horizontally as the pins move vertically (Paragraph 0027).

Therefore it would have been obvious to one of ordinary skill in the art at the time of the invention to use rollers attached to second end of pins (elements) as taught by Gibson et al in the apparatus of Arai in view of Hirose et al to facilitate vertical movement of wafer in space constrained chuck assemblies (Paragraph 0027).

Claim 24 is rejected under 35 U.S.C. 103(a) as being unpatentable over Arai (US PG PUB No. 2003/0075109) in view of Meares et al (EP 0290218).

Regarding Claim 24: Arai teaches all limitations of the claim except that first end of each element is configured to rotate relative to substrate support.

Meares et al teach an apparatus (Figure 8) that includes a platen (substrate support) P that supports wafer W with the help of plurality of fingers (elements) f1 – f4 and where the fingers f experience rotational motion about pivot arc Pa when the wafer is gripped by the fingers (Column 8, lines 10-30).

Therefore it would have been obvious to one of ordinary skill in the art at the time of the invention to provide for rotational movement of first end of elements as taught by Meares et al in the apparatus of Arai to properly engage and disengage the wafer (Column 1, lines 45-50).

### Conclusion

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Applicant's amendment necessitated the new ground(s) of rejection presented in this Office action. Accordingly, THIS ACTION IS MADE FINAL. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a). A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Rakesh K. Dhingra whose telephone number is (571)-272-5959. The examiner can normally be reached on 8:30 -6:00 (Monday - Friday). If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Parviz Hassanzadeh can be reached on (571)-272-1435. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Rakesh Dhingra

Parviz Hassanzadeh Supervisory Patent Examiner Art Unit 1763